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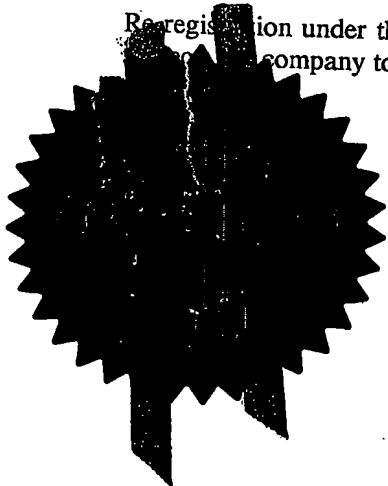
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Method of Making Patterned Retarder

The present invention relates to an improved process for the manufacture of patterned optical retarders for use in such applications as, for example, in polarisation conversion optical systems or LCD projectors and in three-dimensional autostereoscopic displays, and to patterned optical retarders or optically active elements for such patterned optical retarders fabricated by the process.

- 10 It is known to manufacture patterned optical retarders by applying a polymerisable liquid crystal (LC) material to a suitable substrate, aligning the LC layer to a suitable pattern whilst in the LC state, and curing the LC layer to lock in the alignment. The LC layer may be oriented for example by application of an external force (eg electrical or magnetic) or by rubbing the substrate beforehand, which is found to introduce properties to the substrate surface such as to encourage alignment.

The suitably aligned LC layer forms the optically active element of the retarder device, which can then be retained on the original substrate, transferred onto another substrate, given suitable surface treatments and/or used in conjunction with other suitable layers to form a device of desired properties.

25 European patent 89200427 (Phillips, filed 22.02.89) discloses a method of manufacturing a laminated optical element using a polymerisable liquid crystal (LC) material. The LC layer is oriented by means of an external force or by rubbing the substrate beforehand. Also disclosed are various methods of physically patterning the LC layer, for example by depositing the LC material onto a surface with the negative of the desired pattern, orienting the LC material by means of an external force, polymerising the LC to fix the

orientation and then removing the LC layer onto another substrate. Another method disclosed is the patterning of the LC layer by irradiating it through a mask so as to polymerise only selected regions of the LC.

- 5 European patent 0887 667 (Sharp Laboratories of Europe) discloses a method of making a patterned retarder by polymerising birefringent material aligned on a single alignment layer, selectively rubbed in two different directions. The method includes rubbing of an alignment layer uniformly in the first direction, masking with a mask to reveal a second region of the alignment layer and
10 rubbing it through the mask in the second direction, removing the mask, disposing on the alignment layer a layer of birefringent material whose optical axis is aligned by the alignment layer, and fixing the optical axis of the birefringent layer.
- 15 US patent 5861931 (Sharp) discloses a method of making a patterned polarising optical element using photocured liquid crystal material and the use of these elements as a latent parallax barrier in a 3D autostereoscopic display. Odd and even pixels of the LCD display create different images for left and right eyes. The parallax barrier attached to the display artificially restricts the
20 zone where each eye sees its own image. The brain then creates the 3D image.

US 6 222 672 (Sharp) discloses an imaging system with improved achromatic bandwidth. It describes a method of correction of chromatic dispersion in patterned retarder elements in reactive mesogen (RM) made by the multi
25 rubbing technique discussed earlier. Such a patterned retarder includes first patterned retarder regions of half-wave plates having their optical axes oriented at equal but opposite angles followed by an additional half wave plate element with its optical axis at ± 67.5 degree to the first polarisation axis. The patent does not give any details of retarder fabrication, except clear

indication (column 9) that it is made of photocurable liquid crystal RM257 (Merck) patterned by photolithography.

5 EP 0689 084 discloses a linearly photopolymerisable material which may be used as a patterned alignment layer for alignment of birefringent materials. However, in order to produce a retarder having regions of different retarder orientations, two or more photolithographic steps are required in order to expose the linearly photopolymerisable alignment material. These photolithographic steps must be correctly registered with each other, which
10 adds to the complexity of the process and reduces pitch tolerance of the patterned retarder.

The present invention relates in particular to a method for the manufacture of patterned optical retarders which relies upon the aligning properties of a
15 substrate layer onto which a polymerisable liquid crystal (LC) material is applied, and aligned to a suitable pattern whilst in the LC state, and cured to lock in the alignment. It is primarily an alternative to systems based on the use of a single alignment layer, selectively rubbed in two different directions to produce an alignment pattern, such as described in European patent 0887
20 667. Such methods involve multiple steps in the preparation of the alignment layer, particularly when a complex shape is involved, so that the process is laborious and slow and does not lend itself to rapid manufacture and in particular to continuous manufacturing processes.

25 In addition to the known methods of aligning a polymerisable liquid crystal layer to produce patterned retarder elements as above described, a number of other alignment methods are known generally in relation to liquid crystal devices. A number of sources disclose alignment of liquid crystals on microgrooved or microstructured surfaces.

For example "Control of liquid crystal alignment using stamped morphology method" by E.S.Lee et al in Japanese J.Appl.Phys, Vol 32, Pp L1436-L1438 (1993) describes a method of single domain alignment of liquid crystals on an optical alignment polymer layer coated on a heat curable resin layer having microgrooves. US 5 917 570 (DERA) describes the use of surface relief bi-gratings made in photoresist to align liquid crystal materials in a display device. It also mentions that the grating surface can be formed by embossing.

However, it has not been suggested that these methods could be applied in relation to a polymerisable liquid crystal nor do they relate to the manufacture of patterned retarder elements.

It is an object of the present invention to provide an improved process for the manufacture of patterned optical retarders which mitigates some or all of the above disadvantages.

It is a particular object of the present invention to provide an improved process for the manufacture of patterned optical retarders based on prior alignment on a single alignment layer substrate which mitigates some or all of the disadvantages associated with conventional techniques wherein a pattern is applied to the alignment layer by rubbing.

It is a particular object of the present invention to provide an improved process for the manufacture of patterned optical retarders which lends itself to the manufacture of retarders of complex shapes and/or to the rapid and convenient manufacture of retarders in quantity and in particular by continuous processes.

Thus, according to a first aspect of the present invention, a method for the manufacture of patterned optical retarders comprises the steps of:

5

Forming an alignment layer comprising a spatially patterned monograting-like surface relief microstructure formed into a suitable receptive material;
laying down a polymerisable liquid crystal, and in particular a curable liquid crystal such as a photocurable liquid crystal, onto the alignment layer;
5 polymerising the liquid crystal layer to fix the alignment.

The present invention is thus a method of fabrication that substantially reduces the number of technological stages, complexity and operational tolerances of fabrication of broad wavelength band patterned retarder elements made of
10 photopolymerisable liquid crystals with improved achromatic performance. A further advantage of the method is that the regions of the patterned retarder are generally more clearly defined than using previous methods.

In essence, the method comprises only three basic steps.
15

First, a spatially patterned monograting-like surface relief microstructure is fabricated whose purpose is to align the polymerisable liquid crystal into the desired pattern for the patterned retarder. The direction of the microgrooves in the surface relief microstructure is defined by the design of the patterned
20 retarder, being the same within one region or zone where the orientation should be in one direction and different in other regions or zones where the orientation should be in a different direction.

The surface relief microstructure is fabricated in any suitably receptive
25 material to form an alignment layer. This layer may be first deposited on a suitable supporting substrate or may integrally form such a supporting substrate. This substrate may comprise the substrate eventually used in the device or a part thereof, or the optically active aligned LC layer may subsequently be transferred to an alternative substrate material.

30

Second, a suitable polymerisable liquid crystal is coated on top of the surface relief pattern. Interactions between the liquid crystal and the surface relief pattern result in an ordered alignment of the liquid crystal through the thickness of the coated film. The optical axis of different regions of the liquid crystal is determined by the direction of the microgrooves of the surface relief structure beneath it.

The third stage is the polymerisation or curing of the liquid crystal so as to lock in its alignment, and so produce a layer adapted to serve as the optically active basis of the retarder.

In one embodiment of the invention a polymerisable liquid crystal is deposited on single alignment layer. In an alternative embodiment of the invention a plurality of laterally spaced alignment layers may be used with liquid crystal material therebetween. For example two alignment layers can be used, one either side of the liquid crystal material to align the liquid crystal layer. The liquid crystal material form a cell between the alignment layers and is then aligned therebetween. The pattern on each alignment layer in this case may be the same or different. This can be used to provide thicker layers, layers with other functionality etc.

Where a pair of alignment layers are used with a liquid crystal material therebetween the gap may be controlled by any suitable manner. This may include laying down a LC layer of controlled predetermined thickness, or using mechanical separators, such as spacer beads or embossed pillars on one or both alignment layers. An excess of LC material can then be deposited between the alignment layers and pressure applied to bring the desired space.

Where a pair of alignment layers are used with a liquid crystal material therebetween to form a cell, further means may be provided to assist in

alignment of LC material within the cell. For example electromagnetic or mechanical forces may be applied to facilitate alignment and/or further alignment layers may be provided in a multilayer laminate structure.

- 5 The arrangement of the spatially patterned monograting-like surface relief microstructure is determined by the application for which the patterned retarder is to be used. For example in the case of a polarisation conversion optical system for an LCD projector it would consist of a series of stripes of width and pitch corresponding to the pitch of the polarisation splitting
10 element. In the case of a parallax barrier for a 3D display it would correspond to a series of stripes of width and pitch determined by the pixel size in the LCD display.

- The spatially patterned monograting-like surface relief microstructure may be
15 made by any suitable known method. For example one or more of the following methods may be suitable: replication from a mould tool (for example embossing (UV cure and thermal), casting, injection moulding), holography, e-beam writing, laser writing, photolithography, diamond machining or mechanical ruling.

20

In the case of photolithography for example, a photoresist material can be exposed using a photomask that has both the required pattern for the macroscopic spatial patterning of the microstructure and the microscopic pattern for producing the microstructure itself.

25

- The most preferred embodiment of the invention is where a replication method is used to produce the surface relief microstructure. In this preferred embodiment the first general method step comprises the two stages of first
30 creating a mould tool comprising a spatially patterned monograting-like surface relief microstructure and then forming the surface relief pattern into a

suitable receptive material using the said mould tool. This may be done for example by embossing (UV cure and thermal), casting or injection moulding. Preferably, a micromoulding technique is used to form the surface relief pattern.

5

In a particular refinement of the method, a single master is first created comprising a spatially patterned monograting-like surface relief microstructure and this single master is then used to prepare one or more mould tools as above described. The mould tool may be in any suitable form for the moulding process envisaged. For example a mould tool having a plate geometry might be suitable. However in a preferred embodiment, especially for application to continuous production processes, the mould tool is preferably in the form of a roller, and in particular preferably presents a substantially join free and fully circumferential external surface thereon.

15

In one alternative this is done by: forming a master pattern having a contoured metallized surface which conforms to the required relief structure, electroforming a layer of a first metal onto the metallized surface to form a metal master, releasing the metal master from the master pattern, repeating the electroforming process to form a metal embossing shim, whether a shim plate or in the preferred embodiment a join-free metal shim tube, and embossing the relief structure into a polymer film so as to provide an embossed film having the desired mould features.

25 One of the advantages of this route is that the complex spatially patterned monograting-like surface relief microstructure need only be made once as the master and then a more robust mould tool made from it by electroforming (for example in nickel) or by casting in some polymers (eg rubber), glasses or a low melting point metal. The mould tool can then be used to make many
30 replicas. The master plate can for example be produced by one or more of the

following methods: holography, e-beam writing, laser writing, photolithography, diamond machining or mechanical ruling. If desired, the master plate itself can be used as the mould tool. Surface release treatments can be applied to the mould tool to prolong its lifetime and aid release.

5

The present invention may be used to produce a surface relief microstructure having a plurality of zones of different alignment (and hence a retarder having a plurality of such zones). Such a structure is particularly hard to produce by rubbing, since it is difficult to obtain accurate delineation of the different
10 zones. The different zones may have differently patterned relief microstructures and/or similarly patterned relief microstructures in different orientations.

Optionally, the spatial pattern of the monograting-like surface relief
15 microstructure can be produced by constructing a new master mould tool from a plurality of sub-master mould tools. Each sub-master mould tool may first be made from an unpatterned monograting-like surface relief microstructure. The different alignment directions come in this case from the directions in which the sub-master pieces had been cut out and reconstructed to make the new
20 master mould tool. This new master mould tool can be then converted into an embossing mould tool in the desired form.

The preferred replication method is by embossing the surface relief microstructure into a polymerisable polymer material, such as a photocurable
25 polymer resin material, coated as a thin layer onto a suitable substrate. A continuous embossing process is preferred. In this preferred method a relief forming material which comprises an organic or inorganic material or precursor thereof which is polymerisable, and in particular which is curable (whether photocurable such as UV curable, thermally curable, chemically
30 reaction curable or some combination thereof) or thermally formable is

10

applied to a supporting first layer having a receptive surface capable of retaining the relief forming material by reaction forming or micromoulding with use of an advancing line of contact along and progressing across the surface of the supporting layer to provide a surface relief microstructured layer
5 retained on the supporting layer. Where applicable, the surface relief microstructured layer is then cured.

In particular, the technique described in International Patent Application No WO96/35971 and US patent application 08/619,717 and applied in
10 WO98/21626, the contents of which are hereby incorporated herein by reference, is especially preferred.

Thus, the preferred method for creating the surface relief microstructure in a polymerisable polymer material on a flexible substrate comprises the steps of:
15 creating an embossing roller with a surface relief of the dimensions required to form the desired alignment layer surface relief microstructure, with the surface relief running around the circumference of the roller, preferably for substantially the entire circumference in join-free manner;
coating one side of a flexible substrate with a suitable polymerisable polymer
20 material layer and contacting this layer with the embossing roller so as to transfer the alignment microrelief pattern into the polymerisable polymer layer;
polymerising the polymer material layer to form the alignment layer, preferably while in contact with the embossing roller prior to film release.
25

Thus, the preferred method for producing the alignment layer on a rigid or non-transparent substrate comprises the steps of:
forming a line of contact between the receptive surface and at least one mould feature formed in a flexible dispensing layer;

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- applying sufficient of a polymerisable polymeric material to form the relief forming polymer, to substantially fill the at least one mould feature, along the line of contact;
- progressively contacting the receptive surface with the flexible dispensing layer such that the line of contact moves across the receptive surface, and sufficient of the polymer material is captured by the mould feature so as to substantially fill the mould feature;
- polymerising the polymer material filling the at least one mould feature so as to form the relief microstructure; and, optionally, thereafter
- releasing the dispensing layer from the relief microstructured layer.

In either case, the polymerisable polymer material is preferably a resin, capable of being cured.

- The advantage of this method is that the patterned retarder elements may be produced by a continuously running (for example sheet feeding) or reel to reel process. Thereby the process is well suited for high volume production of the patterned retarder elements. Another advantage of this approach is the complete absence of precision lithography.

20

- The liquid crystal may be coated onto the surface relief microstructure to the thickness and tolerance required by a range of coating and printing methods known in the art. Preferred methods include spin coating (for single substrates), precision bead coating or techniques that precisely meter the precise coat thickness such as gravure coating.

25

- Table 1 compares the methods of fabrication of a patterned retarder by multi-rubbing, according to European patent 0887 667 (Sharp), with the method of this invention. It is clear that the new method proposed significantly reduces the number of steps of the process. A further advantage of the proposed

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method is that the patterned retarder elements may be produced by a continuously running or reel to reel process. Thereby the process is well suited for high volume production of the patterned retarder elements. Another advantage is the complete absence of precision lithography. It should also be noted that the processing tolerances are reduced compared to the prior art method.

prior art process	Process of current invention
1. Coat substrate with alignment material	1. Coat substrate with UV curable resin
2. Bake alignment material	2. Emboss and cure surface relief microstructure
3. Rub in first direction	3. Coat with polymerisable liquid crystal
4. Coat with resist	4. Polymerise liquid crystal
5. Expose resist through mask	
6. develop resist	
7. Rub over resist in second direction	
8. Flood expose resist	
9. Develop resist	
10. Coat with polymerisable liquid crystal	
11. Polymerise liquid crystal	

Table 1: Comparison of prior art fabrication technique and process of current invention for making patterned retarders.

The supporting layer may be rigid or flexible, but is preferably flexible for application to continuously running or reel to reel processes.

The suitably receptive material may be supported on a range of substrate types including polymers (flexible and rigid) and non-polymers such as glass. The substrate may optionally be pre-coated on either side with either an anti-reflection layer (when the element is to be used in transmission) or a reflective layer.

The period of the monograting-like microstructure may be uniform across the relief patterned area, may be different for different regions of the relief patterned area, or may vary across the relief patterned area. In any event, the period of the monograting-like microstructure is preferably below 5.0 micron, and more preferably below 2.0 micron. The period is preferably at least 0.1 micron and most preferably lies in the range 0.2 to 1.0 micron.

The depth of the monograting-like microstructure may be uniform across the relief patterned area, or alternatively may be different for alternating stripes with different direction of grooves, or may vary across the relief patterned area or between different zones in the relief patterned area. In any event the depth is preferably sub-micron, preferably in the range 0.02 to 1.0 micron and in particular 60nm to 350nm. The depth of the microstructure should be significantly less than the thickness of the liquid crystal film it is being used to align otherwise the microstructure itself will tend to have an adverse effect on the optical retardation properties of the liquid crystal film.

The cross-section shape of the monograting-like microstructure may be symmetric or asymmetric.

One example of a useful optical retarder element is where the macroscopic pattern comprises a series of alternating stripes or bands. Within one stripe, the microgrooves are generally parallel and oriented in a first direction at a first angle to the boundary between the stripes and within an adjacent stripe the microgrooves are generally parallel and oriented in another direction at a second angle to the boundary between the stripes. These angles may lie in the range from 0 to 90, more preferably from 15 to 45 degrees. In one embodiment, these angles are equal and opposite.

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The orientation of the optical axis of the cured LC lies largely along the direction of the microgrooves of the surface relief pattern. In the simplest case therefore one can make a uniform retarder for use in combination with a patterned retarder by using a simple unpatterned monograting surface.

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The suitable receptive material should also have optical and physical properties that do not affect the performance of the phase retarding optical element.

- 10 The material into which the monograting-like surface relief microstructure is fabricated (suitably receptive material) should be one that replicates the surface relief without significant distortion or error.

- 15 In the case where the optical retarder element is designed to operate in transmission, the suitable receptive material should have negligible birefringence (preferably less than 0.00) and should be as transparent as possible over the operating wavelength range of the element.

- 20 In the case where the optical retarder element is designed to operate in reflection, the suitable receptive material may be coated with a metal or multilayer dielectric coating so as to make it reflecting, after it has been patterned with the monograting-like surface relief microstructure and/or the fabricated aligned patterned LC layer may be subsequently transferred to a substrate of or coated with such material.

25

There may or may not be a supporting substrate for the suitable receptive material.

- 30 A range of coating techniques known in the art (for example spin, gravure, roller or K-bar coating) may be used so as to form a uniform coating of liquid

crystal of known and controlled thickness on top of the monograting-like surface relief microstructure. The optical thickness of the liquid crystal layer, along with its birefringence, determines the physical thickness required to obtain the desired retardation of light of a certain wavelength.

5

The polymerisable liquid crystal may be coated from solution (for example using xylene or PGMEA as solvents) or from 100% solids using temperature to control or reduce liquid viscosity. The liquid crystal needs to be in a liquid crystalline phase in order to align before curing. In solution it is normally in the isotropic phase and when the solvent is removed during coating it enters a liquid crystalline phase on the surface of the microstructure.

10

It is desirable that immediately before alignment the layer is put into the isotropic phase to eliminate defects, unwanted ordering etc. In a preferred embodiment of the method, particularly if the liquid crystal is not already in its isotropic phase when applied, then the LC should be transformed (for example by heating) to its isotropic phase and back to a liquid crystalline phase prior to polymerisation.

15

The temperature at which the liquid crystal is polymerised may be varied so as to fine tune the retardation of the element since the higher the temperature the lower the birefringence and hence lower the retardation for a given thickness of liquid crystal layer.

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In the case of the photopolymerisable liquid crystal RM34 (ex Merck) the liquid crystal is cured under nitrogen using a UV lamp.

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A variation of the main process allows the use of two alignment substrates.

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- (a) the surface relief pattern is produced into a suitable receptive material as previously described.
- (b) the polymerisable liquid crystal is coated on top of the surface relief pattern.
- 5 (c) A second surface relief alignment pattern is laminated on top of the liquid crystal
- (d) the polymerisable liquid crystal is polymerised

10 Alternatively, two alignment surfaces are produced and the liquid crystal is metered into the gap between them. The gap may be set by the volume of liquid crystal dispensed or by the use of spacers.

A variation of the main process described above that allows the re-use of the part with the replicated surface relief is described below.

15

- (a) the surface relief pattern is produced into a suitable receptive material as previously described.
- (b) the polymerisable liquid crystal is coated on top of the surface relief pattern.
- 20 (c) the polymerisable liquid crystal is polymerised.
- (d) a layer of adhesive is coated or laminated onto a suitable carrier substrate. Suitable carrier substrate materials are optically transparent over the wavelength range of interest and have low birefringence. For example glass, quartz or one of a range of plastic films such as those
- 25 made from polyethersulphone, polycarbonate, polyarylate, cellulose diacetate, cellulose triacetate, trimethylpent-3-ene, cyclic polyolefins, or similar.
- (e) The surface of the polymerisable liquid crystal film is contacted with the adhesive layer

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(f) the suitable receptive layer and the adhesive coated carrier substrate are separated thereby transferring the polymerised liquid crystal layer onto the adhesive coated layer.

- 5 In order for this process to work successfully, the polymerised liquid crystal layer must adhere more strongly to the adhesive layer than to the suitable receptive material. This is achieved by careful choice of materials for the adhesive and the receptive layers.
- 10 In a further embodiment of the invention, the method may be used repeatedly so as to build up a series of patterned (or uniform) retarder layers so as to give the patterned retarder element improved optical functionality (for example decreasing the variation of the retardation with wavelength). The additional patterned (or uniform) retarder layers may be formed either directly on top of
- 15 the polymerised liquid crystal layer or on the back of the substrate supporting the suitably receptive material.

In a further embodiment of the invention, the substrates are produced, one with the alignment microrelief structure and one with the alignment relief

20 microstructure superimposed on a surface relief structure of a different type (for example micropisms). The two substrates are brought together and the liquid crystal is metered into the gap between them. The gap may be set by the volume of liquid crystal dispensed or by the use of spacers. The liquid crystal layer is then polymerised and optionally one or both of the substrates

25 removed.

Optionally, other layers with other optical functionality, may be introduced into the multilayer element described above by lamination using appropriate pressure sensitive or curing adhesive. For example a sheet of conventional

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uniform linear optical retarder film may be included or a sheet of dyed film to give a colour effect or to act as a colour filter.

The aligned LC layer forms the optically active element of the retarder device, which can then be retained on the original substrate, transferred onto another substrate, given suitable surface treatments and/or used in conjunction with other suitable layers to form a device of desired properties.

Thus, in a further aspect, a method for the manufacture of patterned optical retarders comprises the steps above described of forming an alignment layer comprising a spatially patterned monograting-like surface relief microstructure into a suitable receptive material; laying down a polymerisable liquid crystal, and in particular a curable such as a photocurable liquid crystal, onto the alignment layer; and polymerising the liquid crystal layer to fix the alignment so as to produce a liquid crystal element for an optical retarder, and the further step of transferring the liquid crystal layer to a suitable secondary substrate, which may be preselected and/or subsequently coated/heated for other desired optical or other properties, and optionally the further step of removing from the liquid crystal element the alignment layer and/or any primary substrate onto which the alignment layer was previously deposited.

In a further aspect, the invention comprises a patterned optical retarder or a liquid crystal element for use in an optical retarder manufactured by the foregoing method. In particular, a patterned optical retarder or a liquid crystal element for use in an optical retarder comprises an alignment layer comprising a spatially patterned monograting-like surface relief microstructure fabricated from a suitable pattern-receptive material, and optionally layed down upon a supporting substrate; and an optically active layer of aligned polymerised liquid crystal material.

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Preferred features of these further aspects, and in particular of the material, and of the fabrication and structure of the surface relief microstructure, will be understood by analogy with the foregoing.

- 5 The invention will now be described by way of illustration in the form of certain examples and with reference to figures 1 to 6 of the accompanying drawings in which:

10 Figure 1 illustrates an embodiment of the inventive process to produce a patterned retarder element;

Figure 2 illustrates a surface profile of an example grating for use in the method of the invention;

Figure 3 shows transmission data for optical retarder;

Figure 4 shows surface relief profiles for an example device;

15 Figure 5 shows a transmission spectrum for an example device;

Figure 6 shows a transmission spectrum for an example device.

20 Figure 1 illustrates an embodiment of the inventive process to produce a patterned retarder element. Optional step 1 is to make a mould tool, step 2 is to produce the surface relief pattern on a suitable material by suitable means, step 3 is to coat and cure the polymerisable liquid crystal to lock in the alignment and orientation of the liquid crystal. Examples of suitable material combinations follow.

25 Example 1

This example describes the fabrication of a phase retarding optical element by means of the improved process described in the main text of the patent.

A monograting surface relief profile was manufactured on the surface of a nickel plated roller by means of single point diamond turning. The surface profile of the resultant grating was recorded by Atomic force microscopy (AFM) and is shown in Figure 2.

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The period of the grating was $0.3\text{ }\mu\text{m}$ and the depth of the grating was 60 nm . The roller was used to make a flexible mould tool by coating a $175\text{ }\mu\text{m}$ thick PET film (Melinex grade 565) with special formulated UV curable acrylate resin and embossing the surface relief grating from the roller into the UV cured acrylate resin. The UV embossing was carried out as described in WO96/35971 at a speed of 0.5 min/in and nip pressure of 2.5 bar . The resin was cured with a UV lamp system using a fluence of approximately 180 J/cm^2 at a peak output wavelength of 365 nm . The thickness of the embossed cured resin layer on the PET film was $3\text{ }\mu\text{m}$.

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Using the same process as for the fabrication of the flexible mould tool, the flexible mould tool was used to UV emboss the surface relief grating into a coating of a second UV curable acrylate resin (the suitable receptive material) on a glass plate. The thickness of the embossed cured resin layer on the glass was $3\text{ }\mu\text{m}$.

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The resultant part was spin coated using a 40% by weight solution of photocurable liquid crystal RM34 (ex Merck) in xylene. The spin speed used was 2350 rpm with a dwell time of 30 s . This spin speed was chosen so as to give a cured film thickness that acts as a half wave plate for light with a wavelength of 550 nm . Since the difference in refractive index between the ordinary and extraordinary rays in the aligned and cured LC film was measured to be 0.1545 at 590 nm , the required thickness of the RM film in this

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case is 1.8 μm . The coated RM film was cured under nitrogen at 20 °C using a UV lamp with a power output of 1 mW/cm² for 20 min.

The finished optical part was tested by recording the transmission as a function of wavelength between parallel polarisers. The transmission was found to fall to a minimum of approximately 1% at a wavelength of 550 nm, indicating that the RM34 layer was aligned and acting as a half wave plate (see figure 3).

10 Example 2

This example describes the fabrication of a phase retarding optical element using a surface relief grating of different shape and amplitude to example 1.

15 An optically recorded reflective monograting was obtained from Spectragon UK Ltd, Glenrothes, Fife. The grating was specified as 3300 lines/mm (0.3 μm pitch). The grating was specified for operation in the visible (400 to 700 nm). AFM analysis of the grating showed it to be nearly sinusoidal in shape with a depth of 80 nm. A nickel embossing shim was grown by
20 electroforming from this master plate. AFM analysis of the nickel shim showed that the grating profile had been replicated with no change in the pitch and a small reduction in the depth to between 62 and 65 μm . The nickel embossing shim was used to make a flexible mould tool by coating a 175 μm thick PET film (Melinex grade 505) with specially formulated UV curable
25 acrylate resin and embossing the surface relief grating from the nickel shim into the UV cured acrylate resin. The UV embossing was carried out as described in WO96/35971 at a speed of 0.5 m/min and nip pressure of 2.5 bar. The resin was cured with a UV lamp system using a fluence of approximately

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180 J/cm² at a peak output wavelength of 365 nm. The thickness of the embossed cured resin layer on the PET film was 3 µm.

Using the same process as for the fabrication of the flexible mould tool, the flexible mould tool was used to UV emboss the surface relief grating into a coating of a second UV curable acrylate resin (the suitable receptive material) on a glass plate. The thickness of the embossed cured resin layer on the glass was 3 µm.

10 The resultant part was spin coated using a 40 % by weight solution of photocurable liquid crystal E70 (Merck) in xylene. The spin speed used was 1600 rpm with a dwell time of 40s. This spin speed was chosen so as to give a cured film thickness that acts as a half wave plate for light with a wavelength of 575 nm. Since the difference in refractive index between the ordinary and extraordinary rays in the aligned and cured LC film was measured to be 0.1545 at 590 nm, the required thickness of the RM film in this case is 1.86 µm. The coated RM film was cured under nitrogen at 20 °C using the same UV lamp as for the embossing but with a fluence of 18 J/cm².

20 The performance of the resulting optical retarder part was tested by placing it between parallel polarisers and measuring the transmission as a function of wavelength. The transmission was found to fall to 1% at a wavelength of 575 nm. This indicates that the liquid crystal film has been oriented by the surface relief grating.

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Example 3

This example describes the fabrication of a phase retarding optical element using a surface relief grating of different period to example 1 and 2.

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The procedure of example 2 was repeated except using a grating specified as 2400 lines/mm (0.4 μ m pitch). The grating was specified for operation in the visible (400 to 700 nm). The measured optical performance of the half wave plate was very similar to that of example 2.

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Example 4

This example describes the fabrication of a phase retarding optical element using the transfer process described in the text. Also this example shows how elements can be successfully made using surface relief gratings of different pitch, amplitude and shape.

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A series of three monogratings type surface relief patterns were fabricated by diamond machining into the surface of nickel coated rollers. The shape of the tool and the pitch of the pattern were varied. The resultant surface relief profiles was recorded by AFM and are shown in Figures 4 a, b and c.

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Each of these rollers in turn was taken and used to make a flexible mould tool by coating a 100 μ m thick PET film (Melinex grade 505) with specially formulated UV curable acrylate resin and embossing the surface relief grating from the roller into the UV cured acrylate resin. The UV embossing was carried out as described in WO96 35971 at a speed of 0.5 m/min and nip pressure of 2 bar. The resin was cured with a UV lamp system giving a fluence of approximately 180 J/cm² at a peak output wavelength of 365 nm. The thickness of the embossed cured resin layer on the PET film was 5 μ m.

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The resultant parts were spin coated using a 40 weight % solution of photocurable liquid crystal RM34 (ex Merck) in xylene. The spin speed used was 2350 rpm with a dwell time of 30s. This spin speed was chosen so as to give a cured film thickness that acts as a half wave plate for light with a

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wavelength between 450 and 550 nm. Since the difference in refractive index between the ordinary and extraordinary rays in the aligned and cured LC film was measured to be 0.1545 at 550 nm, the required thickness of the RM film in this case is between 1.5 and 1.9 μm . The coated RM film was cured under
5 nitrogen at 20 °C using a UV lamp with a power output of 1 mW/cm² for 20 min.

A layer of UV curing acrylate resin adhesive was coated on top of the cured liquid crystal film by spin coating. Spin speed was 3000 rpm and dwell time
10 was 30s. The thickness of the adhesive film layer was 16 μm . The adhesive coated film was laminated at room temperature onto a 1.1 mm thick borosilicate glass plate by passing the film and glass through a nip between two rollers. A nip pressure of 4 psi was used. The adhesive layer was cured
15 by placing the laminated part under a UV lamp with a power output of 1 mW/cm² for 15 min. Finally, the PET film was peeled off to leave the cured and aligned liquid crystal film on the surface of the glass.

The finished optical parts were tested by recording the transmission as a function of wavelength between parallel polarisers. All three different
20 gratings caused alignment of the liquid crystal film, as evidenced by the presence of a transmission minimum between parallel polarisers in the wavelength range 450 to 550 nm. Figure 5 shows for example the transmission spectrum of the sample obtained from grating (c).

25 Example 5

This example shows the effect of coating the finished part with an index matching layer so as to reduce the effect of optical diffraction when the
grating pitch is larger than 0.4 μm .

The three samples prepared in example 4 were taken and a UV-cured coating of Norland 61 was spin coated onto them so as to reduce the effect of diffraction from the surface relief grating used to align the liquid crystal film. The refractive index of this material is 1.56 (between the indices of the o and e-rays, 1.54 and 1.69 respectively). Figure 6 shows the spectra obtained prior to coating of the Norland 61 onto the sample from grating (c) and afterwards. The transmission in the blue part of the spectrum has been significantly increased by the index matching film. The effect is most noticeable for the 1 μ m period grating since its diffraction efficiency is highest in this part of the spectrum.

1/6

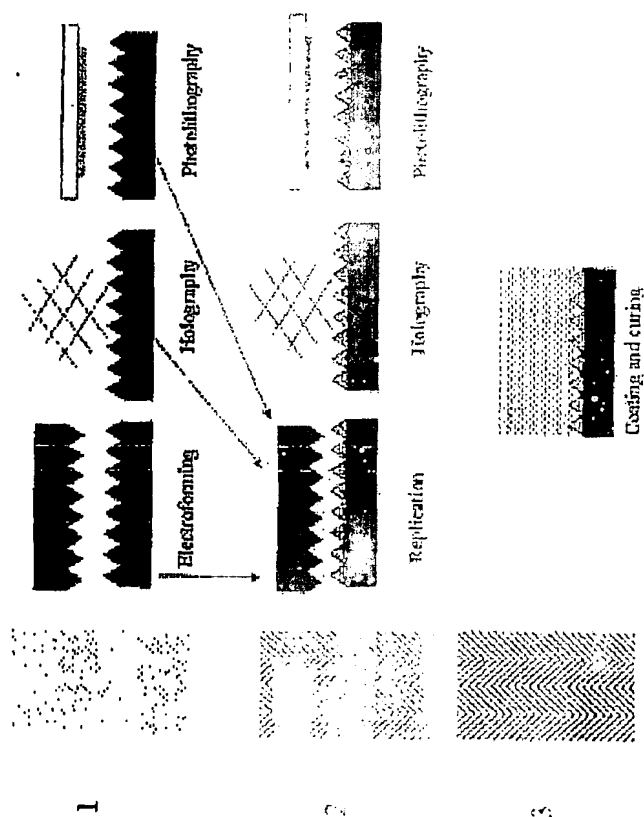


Figure 1: Fabrication process for patterned refractive element. Optional step 1 is to make a mould tool, step 2 is to produce a face relief pattern in a suitable material by suitable means, step 3 is to coat and cure the patterned surface to lock in the alignment and orientation of the liquid crystal.

2/6



Fig. 1: Schematic profile of diamond turned surface rel. direction

3/6

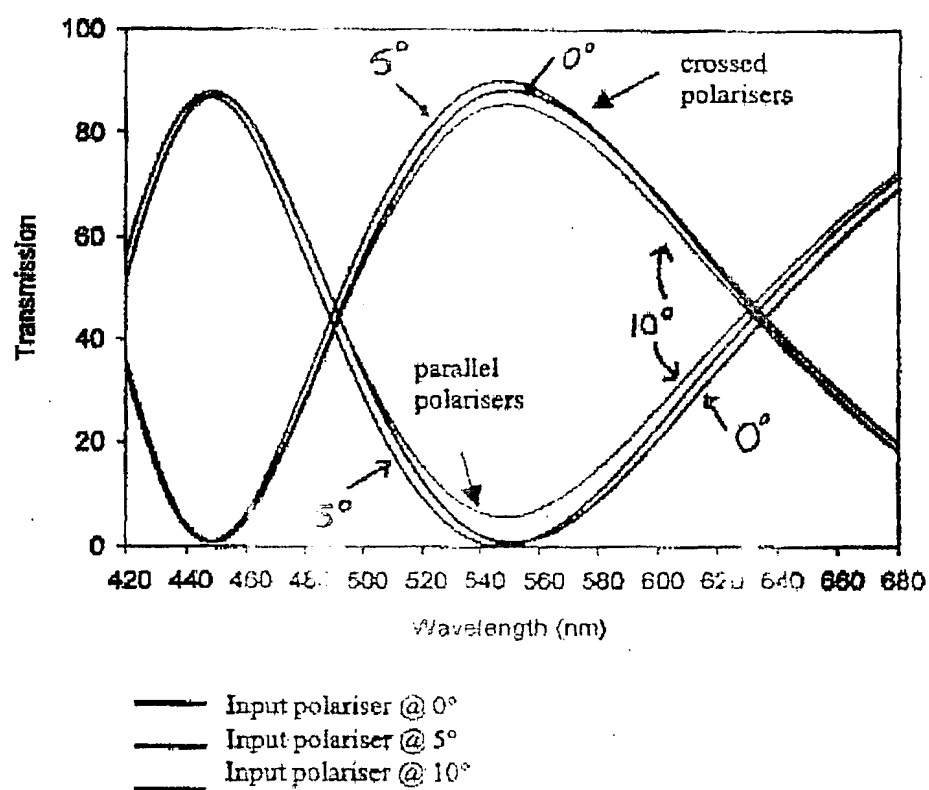


Figure 3: Transmission (in %) of optical retarder part between polarisers as a function of wavelength showing minimum at 550 nm.

4/6

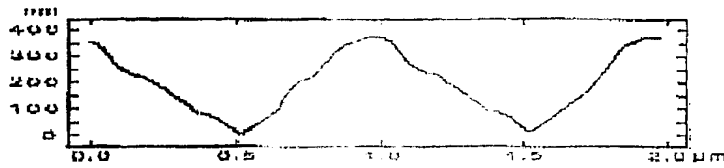


Figure 4a: Saw tooth surface relief profile with 1µm pitch and depth of 350 nm.

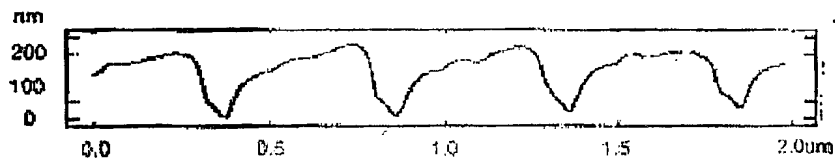


Figure 4b: Asymmetric saw tooth surface relief profile with 0.5µm pitch and depth of 120 nm.

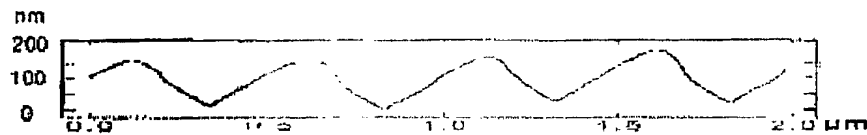


Figure 4c: Saw tooth surface relief profile with 0.5µm pitch and depth of 130 nm.

4/6

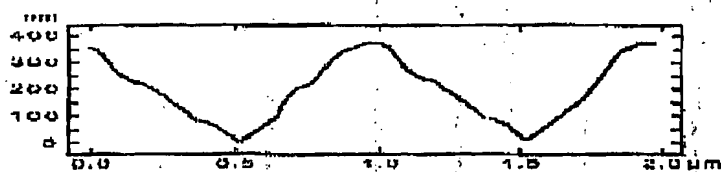


Figure 4a: Saw tooth surface relief profile with 1µm pitch and depth of 350 nm.

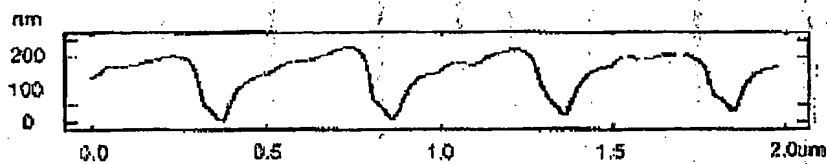


Figure 4b: Asymmetric saw tooth surface relief profile with 0.5µm pitch and depth of 120 nm.

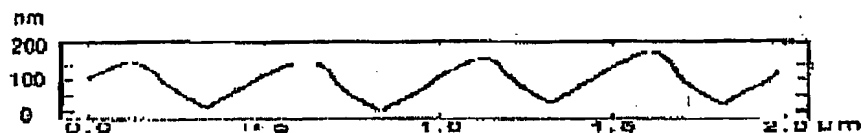
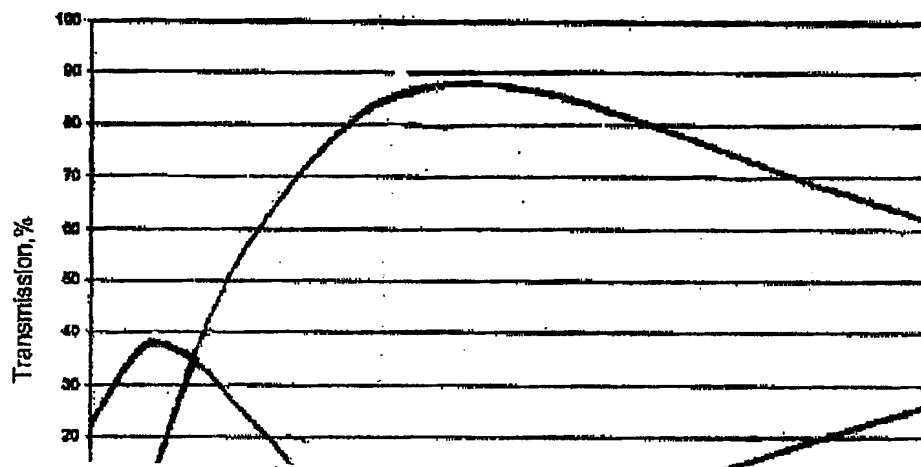


Figure 4c: Saw tooth surface relief profile with 0.5µm pitch and depth of 180 nm.

5/6



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